PRESS RELEASE

From NANONEX

NANONEX DELIVERS VERSATILE NANOIMPRINT TOOL TO THE UNIVERSITY OF MARYLAND

Princeton NJ, November 29, 2004: Nanonex Corp., the world-leading developer and manufacturer of nanoimprint lithography solutions, recently announced the delivery of their NX-2000, Universal Nanoimprintor, to The Laboratory for Physical Sciences (LPS). The nanoimprintor has been installed in a newly renovated nanotechnology lab at the LPS, a unique and world-renowned research institution associated with the University of Maryland in College Park, MD. The machine will be utilized by a multidisciplinary team of scientists in the pursuit of both fundamental and applied research directed toward the development of state-of-the-art, advanced nanoscale devices.

"We find the NX-2000 easy to use and versatile because it combines hot and cold embossing with the capability to perform other types of soft lithographic printing. With the nanoimprintor we are developing device fabrication techniques utilizing a diverse set of materials and novel structures important for the advancement of nanotechnology"

Daniel R. Hines,
Research Staff, UMD

Nanoimprint lithography (NIL) is a breakthrough method of nanopatterning and a revolutionary solution to nanomanufacturing. NIL patterns nanostructures by physical deformation of a material to replicate structures on a mold. NIL can have sub 5nm resolution and 1% CD control, and simultaneously achieve high-throughput and low cost – a feat currently impossible using other existing lithographic methods. The NX-2000® is capable of performing all aspects of thermal nanoimprint, as well as photo-curable nanoimprinting and direct nanopatterning. The company and its proprietary technology has been developed on the pioneering research of renowned expert Prof. Stephen Y. Chou, Founder and Chairman of the firm.

About Nanonex Corp.
Headquartered in Monmouth Junction, NJ with offices in California, Nanonex provides a complete line of nanoimprint lithography (NIL) technology solutions including tools, masks, polymers, and processes. Nanonex NIL solutions offer sub 10nm feature resolution, 3D patterning, large area uniformity, accurate overlay alignment, high-throughput, and low cost. Nanonex NIL solutions include all forms of nanoimprinting, such as thermal plastic, uv-curable, thermal curable, and direct imprinting (embossing). Nanonex NIL solutions can meet the needs of a broad spectrum of markets, such as optical devices, displays, data storage, biotech, IC, chemical synthesis, and advanced materials. Visit www.nanonex.com for additional information.

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For more information, please call Nanonex at 732-355-1600